Erratum to: Antireflective properties of AZO subwavelength gratings patterned by holographic lithography

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Due to a processing error the presentation of Figs. 1 and 5 was incorrect. The corrected Figs. 1 and 5 are given here:

Fig. 1 Schematic diagram of the pattern transfer process steps for the fabrication of the SWG structures of AZO deposited on Si substrate

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Fig. 5 (a) Measured and calculated reflectance spectra of the fabricated AZO SWG structures on Si substrate using 150 nm and 220 nm thick PRs, and (b) calculated reflectance spectra of AZO SWG struc-

tures with 300 nm and 400 nm heights on Si substrate. The *inset* of (a) shows the SEM images of 220 nm thick PR patterns and AZO SWG structure with hole arrays after 3 min RIE